

[ABSTRACT]

Provided is a resist composition including a resin component (A1) that has a constitutional unit (a1) containing an acid decomposable group whose polarity is increased due to an action of an acid, a constitutional unit (a10) represented by General

5 Formula (a10-1), and a constitutional unit (a5) represented by General Formula (a5-1), and a resin component (Z) that has a constitutional unit (z1) represented by General Formula (z1-1) and no acid dissociable group (in the formulae, Wa^{x1} represents an aromatic hydrocarbon group, Ra^5 represents an acid non-dissociable aliphatic cyclic group in which some carbon atoms forming a ring skeleton may be substituted with

10 oxygen atoms, and Rz^0 represents a hydrogen atom or a hydrocarbon group containing no acid dissociable group).

